

Title (en)

DIAMOND COATINGS ON REACTOR WALL AND METHOD OF MANUFACTURING THEREOF

Title (de)

DIAMANTBESCHICHTUNGEN AUF REAKTORWÄNDEN UND VERFAHREN ZU IHRER HERSTELLUNG

Title (fr)

REVETEMENTS DE DIAMANT SUR PAROI DE REACTEUR ET PROCEDE DE FABRICATION DE CEUX-CI

Publication

EP 1358363 B1 20080716 (EN)

Application

EP 01989716 A 20011121

Priority

- US 0143153 W 20011121
- US 74992500 A 20001229

Abstract (en)

[origin: US6537429B2] A corrosion resistant component of semiconductor processing equipment such as a plasma chamber includes a diamond containing surface and process for manufacture thereof.

IPC 8 full level

C23C 14/06 (2006.01); **C23C 16/44** (2006.01); **B01J 19/02** (2006.01); **C23C 16/02** (2006.01); **C23C 16/27** (2006.01); **C23C 30/00** (2006.01); **H01J 37/32** (2006.01); **H01L 21/205** (2006.01); **H01L 21/3065** (2006.01)

CPC (source: EP KR US)

B01J 19/0073 (2013.01 - EP US); **B01J 19/02** (2013.01 - EP US); **C23C 16/0272** (2013.01 - EP US); **C23C 16/27** (2013.01 - EP US); **C23C 16/44** (2013.01 - KR); **C23C 16/4404** (2013.01 - EP US); **H01J 37/32495** (2013.01 - EP US); **B01J 2219/0231** (2013.01 - EP US); **B01J 2219/025** (2013.01 - EP US); **Y10T 428/26** (2015.01 - EP US); **Y10T 428/30** (2015.01 - EP US); **Y10T 428/31678** (2015.04 - EP US)

Cited by

DE102009044876A1; DE102009044876A8; WO2011073767A2

Designated contracting state (EPC)

AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE TR

DOCDB simple family (publication)

US 2002086501 A1 20020704; **US 6537429 B2 20030325**; AT E401430 T1 20080815; AU 2002228604 A1 20020716; CN 1284880 C 20061115; CN 1488009 A 20040407; DE 60134896 D1 20080828; EP 1358363 A2 20031105; EP 1358363 B1 20080716; JP 2004526054 A 20040826; JP 4358509 B2 20091104; KR 100853972 B1 20080825; KR 20030063475 A 20030728; TW I267563 B 20061201; WO 02054454 A2 20020711; WO 02054454 A3 20020912

DOCDB simple family (application)

US 74992500 A 20001229; AT 01989716 T 20011121; AU 2002228604 A 20011121; CN 01821558 A 20011121; DE 60134896 T 20011121; EP 01989716 A 20011121; JP 2002555455 A 20011121; KR 20037008678 A 20030626; TW 90130003 A 20011204; US 0143153 W 20011121